a valve connected between the vaporizer and the processing system, the valve having a valve input connected to a vaporizer output and a first valve output connected to a processing system input and a second valve output connected to a bypass line; and

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a controller for switching the valve between the first valve output and the second valve output.

2. The apparatus of claim 1, further comprising:

a second valve connected between a carrier gas source, a divert gas source and the vaporizer, the second valve having a first valve input connected to the carrier gas source, a second valve input connected to the divert gas source, and a valve output connected to a vaporizer input.

- 3. The apparatus of claim 2, wherein the controller is connected to switch the second valve between the first valve input and the second valve input.
- 4. (Amended) The apparatus of claim 3, wherein the controller is connected to correspondingly switch the valve and the second valve.



- 5. (Amended) An apparatus for processing a substrate, comprising:
 - a chamber having a gas input;
 - a vaporizer;
- a valve connected between the vaporizer and the chamber, the valve having a valve input connected to a vaporizer output and a first valve output connected to the gas input and a second valve output connected to a bypass line; and
- a controller for switching the valve between the first valve output and the second valve output.
- 6. The apparatus of claim 5, further comprising:
- a second valve connected between a carrier gas source, a divert gas source and the vaporizer, the second valve having a first valve input connected to the carrier gas

source, a second valve input connected to the divert gas source, and a valve output connected to a vaporizer input.

- 7. (Amended) The apparatus of claim 5, further comprising: at least one intermediate valve connected between a gas source and the valve.
- 8. (Amended) The apparatus of claim 7, wherein the gas source comprises a plurality of gas supplies.
- 9. (Amended) The apparatus of claim 5, further comprising: at least one input valve connected between a gas source and the valve, the input valve having a plurality of inputs selectably connected to a plurality of gas supplies of the gas source and an output connected to the valve input.
- 10. (Amended) The apparatus of claim 9, wherein the controller is connected to switch the input valve between a first valve input of the plurality of inputs and a second valve input of the plurality of inputs.
- 11. (Amended) The apparatus of claim 10, wherein the controller is connected to correspondingly switch the valve and the input valve.
- 12. A method for delivering processing gas from a vaporizer to a processing system, comprising:

connecting a valve between the vaporizer and the processing system, the valve having a valve input connected to a vaporizer output and a first valve output connected to a processing system input and a second valve output connected to a bypass line; and selectively switching the valve between the first valve output and the second valve output.

13. The method of claim 12, further comprising: stabilizing a vaporizer output before switching the valve to the first valve output.

14. The method of claim 12, further comprising:

initiating vaporization of a source material before a vaporized gas of the source material is needed for processing while the valve is switched to the second valve output; and

switching the valve to the first valve output when the vaporized gas of the source material is needed for processing.

15. The method of claim 12, further comprising:

connecting a second valve between a carrier gas source, a divert gas source and the vaporizer, the second valve having a first valve input connected to the carrier gas source, a second valve input connected to the divert gas source, and a valve output connected to a vaporizer input; and

selectively switching the second valve between the first valve input and the second valve input.

- 16. The method of claim 15 wherein the first and second valves are correspondingly switched.
- 17. An apparatus for delivering processing gas from a vaporizer to a processing system, comprising:

a valve means for selectively delivering gas to a processing system input and to a bypass line, the valve means connected between the vaporizer and the processing system; and

a controller means for switching the valve means between the processing system input and to a bypass line.

18. The apparatus of claim 17 wherein the valve means comprises a valve having a valve input connected to a vaporizer output and a first valve output connected to a processing system input and a second valve output connected to a bypass line.